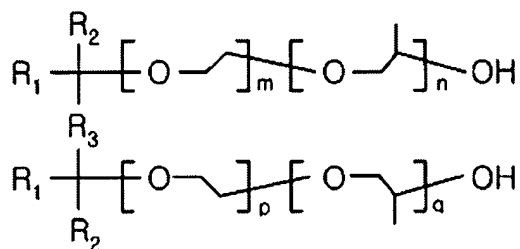


CLEANING SOLUTION USED IN PROCESS OF FABRICATING SEMICONDUCTOR DEVICE

5

ABSTRACT OF THE DISCLOSURE

A cleaning solution used in processes of fabricating semiconductor devices is disclosed. The cleaning solution includes deionized water and a surfactant represented by the following formula:



10

wherein R_1 and R_3 are carbides or fluorocarbons having 1 to 20 carbons, R_2 is hydrogen or carbide, $m+p$ is an integer from 1 to 30, $n+q$ is an integer from 0 to 10, and the surfactant is about 0.01 to about 1.0 wt.% based on the total weight of the deionized water.